

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	3	("3354022").PN.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/03/18 18:03
S2	1006	(216/2).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/03/18 18:05
S3	458	((hydrophobic or water-repell\$5) and etch\$3).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/03/18 18:06
S4	178	((hydrophobic or water-repell\$5) and etch\$3 and silicon).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/03/18 18:06
S5	215	(hydrophobic or water-repell\$5).ti. and etch\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/03/18 18:07
S6	89	(hydrophobic or water-repell\$5).ti. and etch\$3 and silicon	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/03/18 18:13
S7	550	(hydrophobic or water-repell\$5).ti. and (die or etch\$3 or mold)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/03/18 18:13
S8	31	(hydrophobic or water-repell\$5).ti. and (die or etch\$3 or mold).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/03/18 18:22
S9	9	(fluoroalkylsilane and etch\$3).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/03/18 18:22

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S10	81	(hydrophobic or water-repell\$5).ti. and fluoroalkylsilane\$1	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/03/18 18:23
S11	0	(hydrophobic or water-repell\$5) and fluoroalkylsilane\$1 and etch\$3	EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/03/18 18:24
S12	530	(hydrophobic or water-repell\$5 or fluoroalkylsilane\$1) and etch\$3	EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/05/03 14:02
S13	526	(hydrophobic or water-repell\$5) and etch\$3	EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/03/18 18:25
S14	4	fluoroalkylsilane\$1 and etch\$3	EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/03/18 18:24
S15	400	(hydrophobic or water-repell\$5) and mold	EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/03/18 18:25
S16	714	(428/161).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/05/03 13:16
S17	17	(hydrophobic or water-repell\$5) and S16	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/05/03 13:20
S18	23211	(hydrophobic or water-repell\$5) and (etch\$3 or photolithograph\$4 or lithograph\$7)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/05/03 13:21
S19	401	(hydrophobic or water-repell\$5) and (etch\$3 or photolithograph\$4 or lithograph\$7)	JPO	OR	OFF	2006/05/03 13:21
S20	44	(hydrophobic or water-repell\$5) and (etch\$3 or photolithograph\$4 or lithograph\$7) and silicon	JPO	OR	OFF	2006/05/03 13:25
S21	1924	(hydrophobic or water-repell\$5).clm. and (etch\$3 or photolithograph\$4 or lithograph\$7) and silicon	US-PGPUB; USPAT	OR	OFF	2006/05/03 13:26
S22	911	(hydrophobic or water-repell\$5).clm. and (etch\$3 or photolithograph\$4 or lithograph\$7) same silicon	US-PGPUB; USPAT	OR	OFF	2006/05/03 13:26

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S23	277	(hydrophobic or water-repell\$5).ab. and (etch\$3 or photolithograph\$4 or lithograph\$7) same silicon	US-PGPUB; USPAT	OR	OFF	2006/05/03 13:31
S24	1882	(hydrophobic or water-repell\$5) with (etch\$3 or photolithograph\$4 or lithograph\$7)	US-PGPUB; USPAT	OR	OFF	2006/05/03 17:49
S25	1028	S24 and silicon	US-PGPUB; USPAT	OR	OFF	2006/05/03 13:32
S26	948	(hydrophobic or water-repell\$5 or fluoroalkylsilane\$1 or polyfluoroethylene or pte or polytetrafluoroethylene) and etch\$3	EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/05/03 14:02
S27	144	(hydrophobic or water-repell\$5 or fluoroalkylsilane\$1 or polyfluoroethylene or pte or polytetrafluoroethylene) and etch\$3 and silicon	EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/05/03 16:45
S28	114	((karasawa near2 yasushi) (mitsuro near3 atobe near3 chino)).in.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/05/03 16:47
S29	26	((karasawa near2 yasushi) (mitsuro near3 atobe near3 chino)).in. and repell\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/05/03 16:49
S30	39	((karasawa near2 yasushi) (mitsuro near3 atobe near3 chino)).in. and (ink adj jet)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/05/03 16:49
S31	9	((karasawa near2 yasushi) (mitsuro near3 atobe near3 chino)).in. and (ink adj jet) and etch\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/05/03 16:50
S32	11861	(hydrophobic or (water adj repell\$4) or water\$1repell\$4) and (ink\$1jet (ink adj jet) or silicon) and etch\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/05/03 16:52
S33	2311	(hydrophobic or (water adj repell\$4) or water\$1repell\$4) and (ink\$1jet (ink adj jet) or silicon) and etch\$3 and (fluoroalkylsilane\$1 or polyfluoroethylene or pte or polytetrafluoroethylene or fluoropolymer\$1)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/05/03 16:53

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S34	349	(hydrophobic or (water adj repell\$4) or water\$1repell\$4).clm. and (ink\$1jet (ink adj jet) or silicon) and etch\$3 and (fluoroalkylsilane\$1 or polyfluoroethylene or pte or polytetrafluoroethylene or fluoropolymer\$1)	US-PGPUB; USPAT	OR	OFF	2006/05/03 17:07
S35	3	(hydrophobic or (water adj repell\$4) or water\$1repell\$4) and etch\$3 and (fluoroalkylsilane\$1 or polyfluoroethylene or pte or polytetrafluoroethylene or fluoropolymer\$1)	JPO	OR	OFF	2006/05/03 16:55
S36	682	photosensitive adj glass and pattern\$3	US-PGPUB; USPAT	OR	OFF	2006/05/03 17:06
S37	592	photosensitive adj glass and etch\$3	US-PGPUB; USPAT	OR	OFF	2006/05/03 17:06
S38	3746	(hydrophobic or (water adj repell\$4) or water\$1repell\$4) and (silicon near10 etch\$3)	US-PGPUB; USPAT	OR	OFF	2006/05/03 17:07
S39	114	(hydrophobic or (water adj repell\$4) or water\$1repell\$4) with (silicon near10 etch\$3)	US-PGPUB; USPAT	OR	OFF	2006/05/03 17:07
S40	1	(hydrophobic or water-repell\$5) with silicon with (etch\$3 and (photoresist or \$5lithography))	US-PGPUB; USPAT	OR	OFF	2006/05/03 17:55
S41	25	(etch with silicon with anisotropic with mask\$3 with oxide) .clm.	US-PGPUB; USPAT	OR	OFF	2006/05/03 18:02
S42	5498	(etch with silicon with mask\$3 with oxide)w near20 (hydrophobic or (water adj repell\$3))	US-PGPUB; USPAT	OR	OFF	2006/05/03 18:04
S43	2	(etch with silicon with mask\$3 with oxide) near20 (hydrophobic or (water adj repell\$3))	US-PGPUB; USPAT	OR	OFF	2006/05/03 18:05
S44	253	(etch with silicon with mask\$3 with oxide) and (hydrophobic or (water adj repell\$3))	US-PGPUB; USPAT	OR	OFF	2006/05/03 18:04
S45	924	(hydrophobic or (water adj repell\$3)) with etch\$3	US-PGPUB; USPAT	OR	OFF	2006/05/03 18:05
S46	646	(hydrophobic or (water adj repell\$3)) with etch\$3 and silicon	US-PGPUB; USPAT	OR	OFF	2006/05/03 18:05
S47	3	("3354022").PN.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/05/03 18:21
S48	23	("3354022").URPN.	USPAT	OR	OFF	2006/05/03 19:05

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S49	2	("2760863").PN.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/05/03 19:06
S50	2	("2760863").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/05/03 19:06